

In re: Hyun-Chul Kim  
Serial No.: 10/663,967  
Filed: September 16, 2003  
Page 3 of 11

The listing of Claims will replace all prior versions, and listings, of claims in the application.

**Listing of Claims:**

Claims 1-8 (Canceled).

9. (Currently Amended) A method of forming an integrated circuit device, comprising:

forming a window layer on an integrated circuit substrate that defines a fuse region such that the window layer is formed at an upper portion of the integrated circuit device and recessed beneath a surface of the integrated circuit device;

forming a conductive layer pattern and a buffer pattern on the integrated circuit substrate between the integrated circuit substrate and the window layer, the buffer pattern being between portions of the conductive layer pattern on the integrated circuit substrate; and

forming a fuse pattern between the buffer pattern and the window layer.

10. (Original) The method of Claim 9, further comprising forming a metal wiring on the integrated circuit substrate, the metal wiring being more remote from the integrated circuit substrate than the window layer.

11. (Currently Amended) The method of Claim 10, wherein forming the buffer pattern comprises forming a first buffer pattern, the method further comprising:

forming a first insulation layer between the first buffer pattern and the fuse pattern, the fuse being formed on the first insulation layer;

forming a second buffer pattern between the first buffer pattern and the integrated circuit substrate; and

forming a second insulation layer between the second buffer pattern and the first buffer pattern, the conductive layer pattern and the first buffer pattern being formed on the second insulation layer.

12. (Original) The method of Claim 11, wherein forming the window layer

In re: Hyun-Chul Kim  
Serial No.: 10/663,967  
Filed: September 16, 2003  
Page 4 of 11

comprises:

- forming a third insulation layer on the first insulation layer;
- forming a passivation layer on the third insulation layer;
- etching the passivation layer and the third insulation layer in the fuse region to the window layer on the fuse pattern that is recessed beneath the surface of the integrated circuit device.

13. (Currently Amended) The method of Claim 11, wherein forming the fuse pattern comprises forming a fuse pattern comprising a first conductive material, wherein forming the conductive layer pattern and the first buffer pattern comprises forming the conductive layer pattern and the first buffer pattern comprising a second conductive material, wherein forming the second buffer pattern comprises forming a second buffer pattern comprising a third conductive material, wherein the second and third conductive materials are different from the first conductive material and wherein the first and second buffer patterns are planar.

14. (Original) The method of Claim 11, further comprising:

- forming a line pattern between the integrated circuit substrate and the second insulation layer adjacent the second buffer pattern;
- forming a contact hole in the first and second insulation layers that exposes a portion of the line pattern; and
- forming a contact plug in a contact hole that electrically couples the fuse pattern to the line pattern.

15. (Currently Amended) The method of Claim 11, further comprising:

- ~~forming a conductive layer pattern between the second insulation layer and the first insulation layer adjacent the first buffer pattern;~~
- forming a third insulation layer on the first insulation layer and the fuse pattern;
- forming a metal wiring on the third insulation layer above the conductive layer pattern;

In re: Hyun-Chul Kim  
Serial No.: 10/663,967  
Filed: September 16, 2003  
Page 5 of 11

forming a via hole in the first and third insulation layers that exposes at least a portion of the conductive layer pattern; and

forming a conductive plug in a via hole that electrically couples the conductive layer pattern and the metal wiring.

16. (Original) The method of Claim 11, wherein forming the integrated circuit device comprises forming an integrated circuit memory device.

17. (Withdrawn) A method of forming an integrated circuit device, comprising:

forming a conductive layer on an integrated circuit substrate, the conductive layer extending from a cell region to a fuse region of the integrated circuit substrate;

patterning the conductive layer to simultaneously form a plate electrode in the cell region and a buffer pattern in the fuse region;

forming a first insulation layer on the plate electrode and the buffer pattern;

forming a metal layer on the first insulation layer that extends from the cell region to the fuse region;

patterning the metal layer to simultaneously form a metal wiring in the cell region of the integrated circuit substrate and a fuse pattern in the fuse region of the integrated circuit substrate;

forming a second insulation layer on the metal wiring and the fuse pattern;

forming a passivation layer on the second insulation layer; and

etching the passivation layer and the second insulation layer in the fuse region of the integrated circuit substrate to form a window layer defining the fuse region.

18. (Withdrawn) The method of Claim 17, wherein forming a conductive layer comprises forming a first conductive layer and wherein forming the buffer pattern comprises forming a first buffer pattern, the method further comprising:

forming a second conductive layer on the integrated circuit substrate extending from the cell region to the fuse region, the second conductive layer being positioned between the integrated circuit substrate and the first buffer pattern; and

In re: Hyun-Chul Kim  
Serial No.: 10/663,967  
Filed: September 16, 2003  
Page 6 of 11

patterning the second conductive layer to simultaneously form a bit line in the cell region and a second buffer pattern in the fuse region.

19. (Withdrawn) The method of Claim 18, wherein forming the second conductive layer further comprises:

forming a first layer of conductive material on the integrated circuit substrate;  
forming a second layers of conductive material on the first layer of conductive material; and

etching the first and second layer of conductive material to simultaneously form the bit line and the second buffer pattern.

20. (Withdrawn) The method of Claim 19 wherein the first layer of conductive material comprises polysilicon and the second layer of conductive material comprises tungsten silicide.

21. (Withdrawn) The method of Claim 18, further comprising forming a third insulation layer between the second buffer pattern and the first buffer pattern.

22. (Withdrawn) The method of Claim 21 wherein forming the first buffer pattern comprises:

forming an fourth insulation layer on third insulation layer in the fuse region of the integrated circuit substrate; and

etching the first conductive layer such that a portion of the first conductive layer remains on the fourth insulation layer in the fuse region of the integrated circuit substrate.

23. (Withdrawn) The method of Claim 17, wherein forming the metal wiring and the fuse pattern comprises:

forming a first layer of a metal on the first insulation layer;

forming a second layer of a metal compound on the first layer;

forming a photoresist pattern on the first and second layers;

In re: Hyun-Chul Kim  
Serial No.: 10/663,967  
Filed: September 16, 2003  
Page 7 of 11

etching the first and second layers according to the photoresist pattern to simultaneously form the metal wiring and the fuse pattern.

24. (Withdrawn) The method of Claim 18 wherein forming an integrated circuit device comprises forming an integrated circuit memory device.

25. (Withdrawn) The method of Claim 24 wherein the integrated circuit memory device comprises a dynamic random access memory (DRAM) device.

26. (New) The method of Claim 9, wherein forming the conductive layer pattern and the buffer pattern comprises simultaneously forming the conductive layer pattern and the buffer pattern.

27. (New) The method of Claim 9, wherein the buffer pattern is directly beneath the fuse pattern.

28. (New) The method of Claim 11, wherein forming the second buffer pattern comprises simultaneously forming the second buffer pattern and a line pattern on the integrated circuit substrate, the second buffer pattern being between portions of the line pattern on the integrated circuit substrate.

29. (New) The method of Claim 14, wherein forming a contact plug comprises forming first and second contact plugs in first and second contact holes, respectively, that electrically couple the fuse pattern to the line pattern, the first and second buffer patterns being between the first and second contact plugs and beneath the fuse pattern.